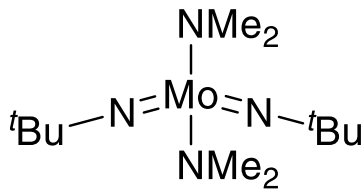


Catalog # 42-0215 Bis(t-butylimido)bis(dimethylamino)molybdenum(VI), 98%



Thermal Behavior:

- Distillation temperature 72 °C/8 Torr [1]
- TGA curve and data is available in [5]
- Vapor pressure: 0.13 Torr/50°C, 0.20 Torr/55°C [5]

Technical Notes:

1. ALD/CVD precursor for molybdenum thin film deposition

Target Deposit	Deposition Technique	Delivery Temperature	Pressure	Co-reactants	Deposition Temperature	Ref.
MoN _x	ALD	40°C	7.5 Torr	NH ₃	210°C-330°C	1-4
MoO ₃	ALD PEALD	50-55°C 50°C	0.3 Torr 7.5 Torr	O ₃ P ^L O ₂	100-300°C 50-350°C	5 6
MoS ₂	PEALD	60°C	0.15 Torr	P ^L H ₂ S	250°C	7
MoC _x N _y	PECVD	80°C	-	P ^L H ₂ /N ₂	150°C	8
Ti _x Mo _{1-x} N	PEALD	60°C	-	T(NMe ₂) ₄ , P ^L N ₂	250°C	9

References:

1. [Chem. Mater. 2007, 19, 263.](#)
2. [Chem. Vap. Deposition 2008, 14, 71.](#)
3. [Thin Solid Films 2008, 516, 6041.](#)
4. [Surf. Coat. Techn. 2008, 202, 5103.](#)
5. [J. Vac. Sci. Technol. A, 2014, 32, 01A119.](#)
6. [J. Vac. Sci. Technol. A, 2016, 34, 01A103.](#)
7. [J. Vac. Sci. Technol. A, 2019, 37, 010907.](#)
8. [Thin Solid Films 2019, 692, 137607.](#)
9. [J. Vac. Sci. Technol. A, 2021, 39, 012407.](#)